

Low-pressure plasma system V15-G

Standard system for cleaning, activation and etching



View into the process chamber.

The system is integrated in a 19" rack, which is equipped with rollers and height-adjustable feet.

A professional PLC control unit serves as a storage for definable process parameters.

System features

- USB port
- Ethernet interface
- Remote maintenance (VPN)
- Microwave coupling from the top
- Swing door

Options

- Vacuum pump
- Ozone trap
- Up to three additional gas inlets
- Additional excitation frequencies (40 kHz, 13.56 MHz)
- Rotary drum for the treatment of bulk material
- Rotary table
- Lateral microwave coupling
- Soft start and slow vent

Technical data

Dimensions of the system (W x D x H): 670 x 900 x 1,850 mm

Dimensions of the chamber (W x D x H): 250 x 250 x 250 mm

Plasma excitation frequency: Microwave (2.45 GHz)

Microwave power: 100-600 W

Gas inlets with mass-flow-control: 1 channel

Power supply: 230/400 V, 50/60 Hz

Power input: 1.5 kVA

Vacuum gauge: Pirani

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The standard system V15-G is designed for the industrial small series production as well as for the low-pressure plasma treatment in R&D laboratories.

